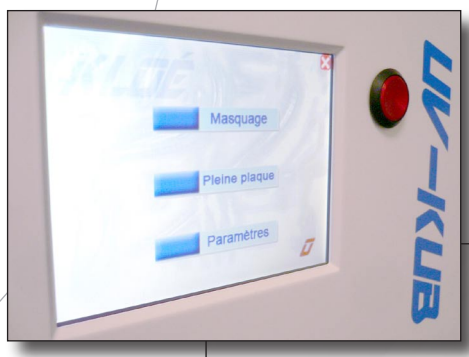
UV - KUB

1 UV LED Exposure System

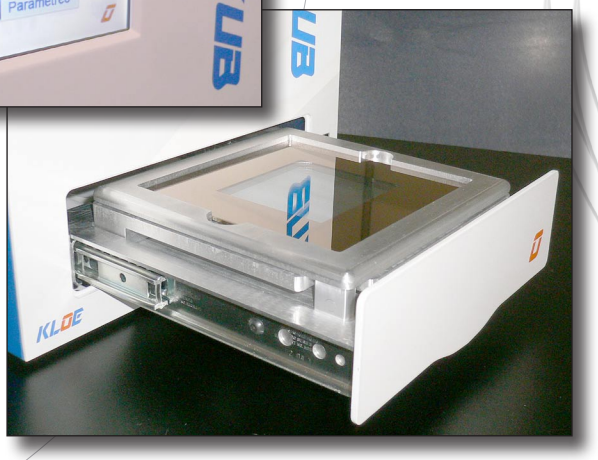
2 UV LED Exposure and Masking System

Kloé has extensive experience in photolithography through its Dilase direct laser writing technology, and presents the UV-KUB system for UV light photosensitive layer curing. The UV-KUB is a UV LED exposure and masking system with available light sources at wavelengths of 365 nm or 385 nm. This is a very compact table-top system capable of exposing a wafer surface area of up to 4 inches in diameter. The UV-KUB system is compatible with hard (physical) or soft (proximity) masking contacts, and features variable mask to substrate distance control.

UV-KUB Specifications	
Resolution	2 µm
Emission spectrum	365 nm ± 5 nm / 385 nm ± 5 nm
Illumination on the surface of a 4 inches wafer	25 mW / cm² ± 10 %
Heating of the wafer during the insolation	< 1°C
Insolation cycle (continuous/discontinuous)	from 1 second to 18 hours
Number of memorized cycles	10
UV-KUB dimensions	260 x 260 x 260 mm³ 10.2 x 10.2 x 10.2 inches
UV-KUB weight	8,2 kg / 18lbs
Color touch screen	5.7 inches diagonal
Power supply	110V or 230V 50Hz
Maximum power consumption	180 Watts



UV-KUB Touchscreen



UV-KUB Tray

Applications

The UV-KUB system is ideal for a breadth of applications in laboratories and R&D groups working with optics, biotechnology, microtechnology, photolithographic processes requiring 1 or 2 masking levels, wafer bonding, simple layer or adhesive reticulation, connections and biological or cells cultures.

Advantages

The UV-KUB exposure and masker has the following advantages :

- A perfectly monochromatic exposure over the wafer surface area, with a bandwidth lower than 10 nm.
- Cold UV exposure and real time in-situ temperature control of the substrate environment providing homogenous exposure over the whole surface, therefore eliminating any undesirable thermal effects.
- A strong power density.
- Long LED lifetime : more than 10 000 hours of controlled real time use.
- User-friendly touch screen interface for exposure cycles programming(continuous or cyclic exposure).
- No warm-up time required.
- Computerized control of UV source intensity adjustment is intuitive and straight forward.
- Air-tight substrate exposure chamber guarantees user safety.
- Automated wafer loading and unloading system.
- Low power consumption.

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